Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
Li	111	(427/567).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 10:19
L2	158	(427/593).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 10:19
13	269	L1 or L2	US-PGPUB; USPAT	OR	ON	2005/10/12 10:19
L4	20	L3 and (hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2")	US-PGPUB; USPAT	OR	ON	2005/10/12 10:22
L5	249	L3 not L4	US-PGPUB; USPAT	OR	ON	2005/10/12 10:22
L6	171	(Bernard.in. or Dijon.in. or Rafin. in.) and (hafnia or ((hafnium or Hf) adj \$30xide) or HfO2 or HfO or "HfO.sub.2")	US-PGPUB; USPAT	OR	ON	2005/10/12 10:38
L7	7	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:39
L8	2	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:39
L10	2	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (vacuum or evaporat\$6 or (electron adj (beam or gun))))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:41
L11	11	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (vacuum or evaporat\$6 or (electron adj (beam or gun))))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:41
L13	10	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (cold or (room adj temperature) or cool\$4))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:42

L14	0	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same (cold or (room adj temperature) or cool\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:42
L15	1	(Bernard in. or Dijon in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same ("without" near3 (energy or ion or plasma or heat\$4)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:42
L16	1	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same ("without" near3 (energy or ion or plasma or heat\$4)))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:42
L17	171	(Bernard.in. or Dijon.in. or Rafin. in.) and (hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2")	US-PGPUB; USPAT	OR	ON	2005/10/12 10:43
L18	7	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:43
L19	2	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:43
L20	11	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (vacuum or evaporat\$6 or (electron adj (beam or gun))))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:43
L21	10	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same (cold or (room adj temperature) or cool\$4))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:43
L22	1	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same ("without" near3 (energy or ion or plasma or heat\$4)))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:44

L23	149	L17 not (L18 or L19 or L20 or L21 or L22)	US-PGPUB; USPAT	OR	ON	2005/10/12 10:43
L25	34	(Bernard.in. or Dijon.in. or Rafin. in.) and (hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2")	USOCR	OR	ON	2005/10/12 10:44
L26	2	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or ((Hf or hafnium) adj \$3oxide) or HfO2 or HfO or "HfO.sub.2") same (reactive near2 evaporat\$5))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:47
L27	7	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or ((Hf or hafnium) adj \$3oxide) or HfO2 or HfO or "HfO.sub.2") same ((ambient or ambiant or room) near2 temperature))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:47
L28	0	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or ((Hf or hafnium) adj \$30xide) or HfO2 or HfO or "HfO.sub.2") same ((ambient or ambiant or room) near2 temperature))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:47
L29	1	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or ((Hf or hafnium) adj \$3oxide) or HfO2 or HfO or "HfO.sub.2") same (reactive near2 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:47
L30	2422	(427/162,164,166).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 10:52
L31	1394	(427/255.23,255.31,255.7).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 10:52
L32	1120	(427/294).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 10:52
L33	456	(427/419.3).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 10:52
L34	1594	(359/584,588,589,838).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 10:52
L35	6567	L30 L31 L32 L33 L34	US-PGPUB; USPAT	OR	ON	2005/10/12 10:52
L36	6567	L30 L31 L32 L33 L34	US-PGPUB; USPAT	OR	ON	2005/10/12 10:52

L37	8	L36 and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5)) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:00
L38	9	L36 and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO:sub.2") with (pore or porous or porous or porous or porous or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5)) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:53
L40	11	L36 and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:54
L41	673	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO, sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:55
L42	189	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:55

L43	189	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:56
L44	8	L43 and ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:56
L45	13	L43 and (cold or (room adj temperature) or cool\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:56
L46	2	L43 and ("without" near3 (energy or ion or plasma or heat\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:56
L47	8	L43 and ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:56
L48	13	L43 and (cold or (room adj temperature) or cool\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:56
L49	2	L43 and ("without" near3 (energy or ion or plasma or heat\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:56
L50	168	L43 not (L47 or L48 or L49)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:56
L51	673	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:57
L52	0	L51 same ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 10:57

L53	23	L51 same ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:58
L55	20	L51 same (cold or (room adj temperature) or cool\$4)	US-PGPUB; USPAT	OR	ON	2005/10/12 10:58
L57	1	L51 same ("without" near3 (energy or ion or plasma or heat\$4))	US-PGPUB; USPAT	OR	ON	2005/10/12 10:59
L58	13	L51 and ((protect\$5 or damag\$5) with laser)	US-PGPUB; USPAT	OR	ON	2005/10/12 10:59
L59	3	((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or amorphus)) and (reactive near2 evaporat\$5) and ((room or ambient or ambiant) near2 temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:21
L60	2	(((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or amorphus)) same (reactive near2 evaporat\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:03
L61	33	(((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2")) same (reactive near2 evaporat\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:05
L62	31	L61 not L60	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:05
L63	105	((hafnia or ((hafnium or Hf) near2 \$3oxide) or HfO2 or HfO or "HfO. sub.2")) and (reactive near2 evaporat\$5) and ((room or ambient or ambiant) near2 temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:10
L64	94	L63 not (L59 or L61)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:10

L76	39	temperature) L72 and (substrate with	USPAT US-PGPUB;	OR	ON	2005/10/12 11:19
L73	39	with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror)) L72 and (substrate with	US-PGPUB;	OR	ON	2005/10/12 11:18
L72	73	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") near3 (amorphous or amorphus)	US-PGPUB; USPAT	OR	ON	2005/10/12 11:16
L71	9	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((evaporat\$5) with (Hf or hafnium) with (O2 or oxygen or "O.sub.2")))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:15
L69	28	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((evaporat\$5) with (Hf or hafnium) with (O2 or oxygen or "O.sub.2")))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:15
L67	2	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((reactive adj evaporat\$5) with (Hf or hafnium) with (O2 or oxygen or "O.sub. 2")))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:14
L66	7	\$5layer or evaporat\$6 or stack or mirror) same (cool\$3 or cold or (room adj temperature))) L65 and L36	US-PGPUB; USPAT	OR	ON	2005/10/12 11:14
L65	326	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or	US-PGPUB; USPAT	OR	ON	2005/10/12 11:14

L79	17	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") near3 (amorphous or amorphus) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:20
L80	4	((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or amorphus)) same ((room or ambient or ambiant) near2 temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:22
L81	413	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (silica or SiO2 or "SiO.sub.2" or SiO or (silicon adj \$30xide)) with (mirror or multilayer or (multi adj layer) or stack or reflect\$6 or (alternat\$6 near2 layer)))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:23
L82	29	L81 and L36	US-PGPUB; USPAT	OR	ON	2005/10/12 11:23
L84		((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2"))) and (temperature near2 room)	US-PGPUB; USPAT	OR	ON	2005/10/12 11:24
L85	29	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2"))) and (temperature with substrate)	US-PGPUB; USPAT	OR	ON	2005/10/12 11:25

L86	2	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2"))) and (temperature with substrate)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:26
L87	0	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2"))) and (temperature near2 room)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:26
L88	22	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2") same (temperature)))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:26
L89	1955	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same temperature)	US-PGPUB; USPAT	OR	ON	2005/10/12 11:27
L90	. 45	L89 and L36	US-PGPUB; USPAT	OR	ON	2005/10/12 11:27
L98	2422	(427/162,164,166).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 11:28
L99	1394	(427/255.23,255.31,255.7).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 11:28
L100	1120	(427/294).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 11:28
L101	456	(427/419.3).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 11:28
L102	1594	(359/584,588,589,838).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/10/12 11:28
L103	6567	L98 L99 L100 L101 L102	US-PGPUB; USPAT	OR	ON	2005/10/12 11:28

L104	19	L103 and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf. sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror)).ti,ab.	US-PGPUB; USPAT	OR	ON	2005/10/12 11:28
L105	101	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or amorphus))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:29
L108	553	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or amorphus))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:30
L109	50	L108 and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf of hafnium))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:30
L111	8	L108 and L103	US-PGPUB; USPAT	OR	ON	2005/10/12 11:32
L112	12	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or amorphus))	USOCR	OR	ON	2005/10/12 11:32
L113	77	("427"/\$).ccls. and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf of hafnium))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:33

L115		((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) and (("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy) with (substrate or base or workpiece or mirror or coat\$4))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:34
L117	2	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) and (("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy) with (substrate or base or workpiece or mirror or coat\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:35
L118	16	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and ((((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) same (temperature with (substrate or base or workpiece or mirror or coat\$4)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:36

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L119	1	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density with (determin\$9 or optimiz\$9 or optimal\$8 or based or depend\$7))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:36
L120	22	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density with (determin\$9 or optimiz\$9 or optimal\$8 or based or depend\$7))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:36
L121	22	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density with (determin\$9 or optimiz\$9 or optimal\$8 or based or depend\$7))	US-PGPUB; USPAT	OR	ON	2005/10/12 11:37
L122	164	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density)	US-PGPUB; USPAT	OR	ON	2005/10/12 11:37
L123	142	L122 not L121	US-PGPUB; USPAT	OR	ON	2005/10/12 11:37
L124	147	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO, sub.2" or Hf2O3 or "Hf.sub.2O, sub.3" or "Hf.sub.2 O.sub.3") near3 (amorphous or amorphus))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:39
L125	32	L124 and ((ambient or room or ambiant) near2 (temperature))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:42
L126	2	L124 and (reactive near2 evaporat\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:42

L127	12	L124 and (electron adj beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/12 11:43
1128	110	1 124 not (1 125 or 1 126 or 1 127)	US-PGPUB:	OR	ON	2005/10/12 11:44
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